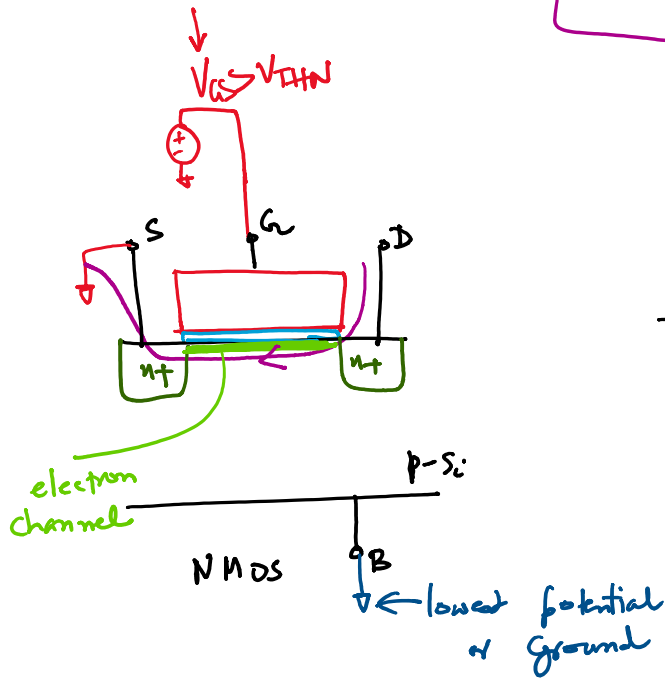


CMos Technology

↳ Complementary Mos (FET)

↳ Mos

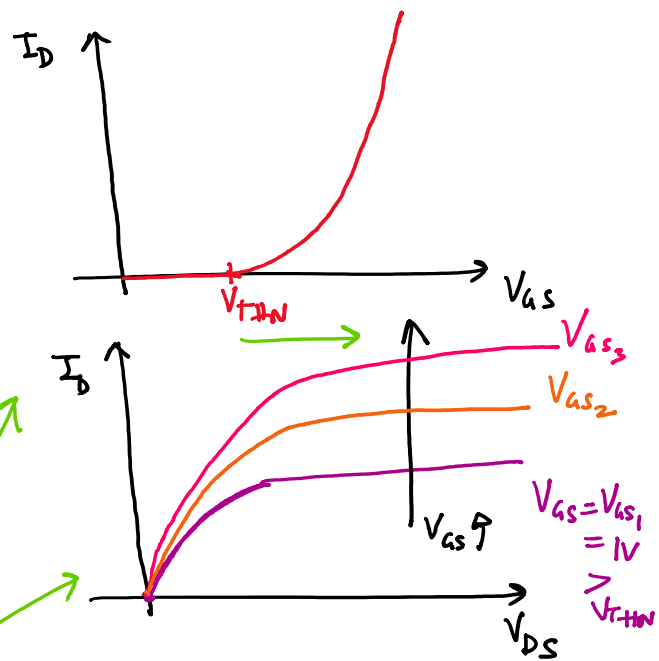
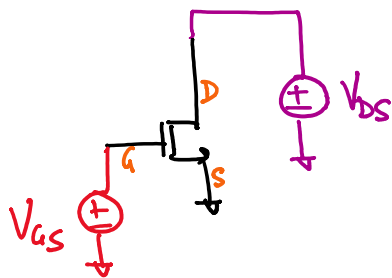
↳ N-type & P-type transistors



a) Accumulation

b) Depletion

c) Inversion



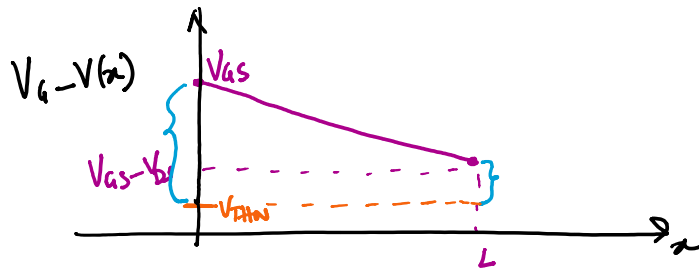
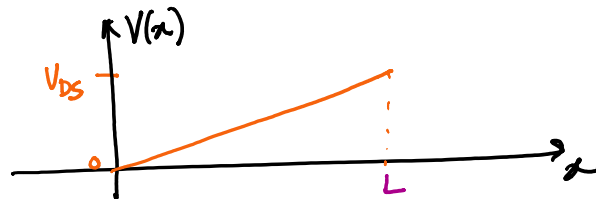
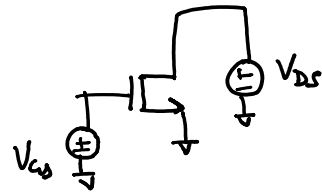
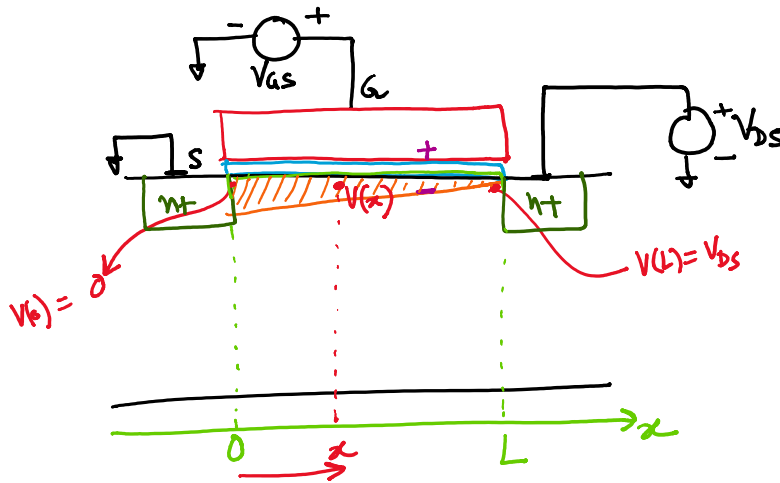
Derive Equations

for $I_D = f(V_{GS}, V_{DS})$

Voltage drop across the gate oxide across the channel

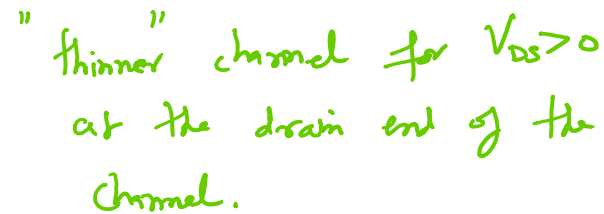
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$L \equiv \text{Length}$



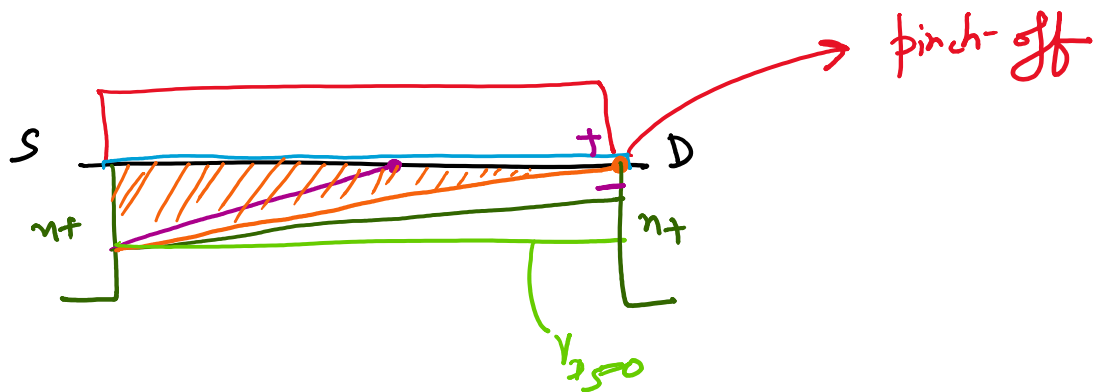
\propto To form a channel under gate oxide,
 $\underline{V_{GS} - V(x) > V_{THN}}$ (Inversion)

→ The density of electrons in the channel follows the trend of $V_{GS} - V(x)$, and falls to a minimum at $x=L$



Channel Pinch-off

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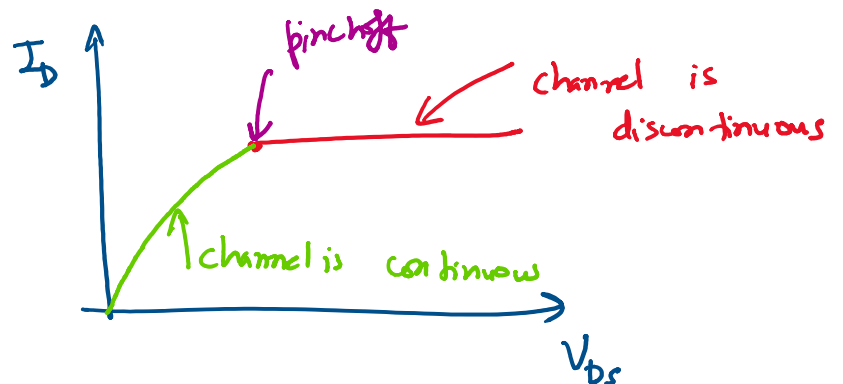


$$V_{gs} - V_{ds} > V_{thn} \text{ for inversion}$$

$$\Rightarrow V_{ds} < V_{gs} - V_{thn}$$

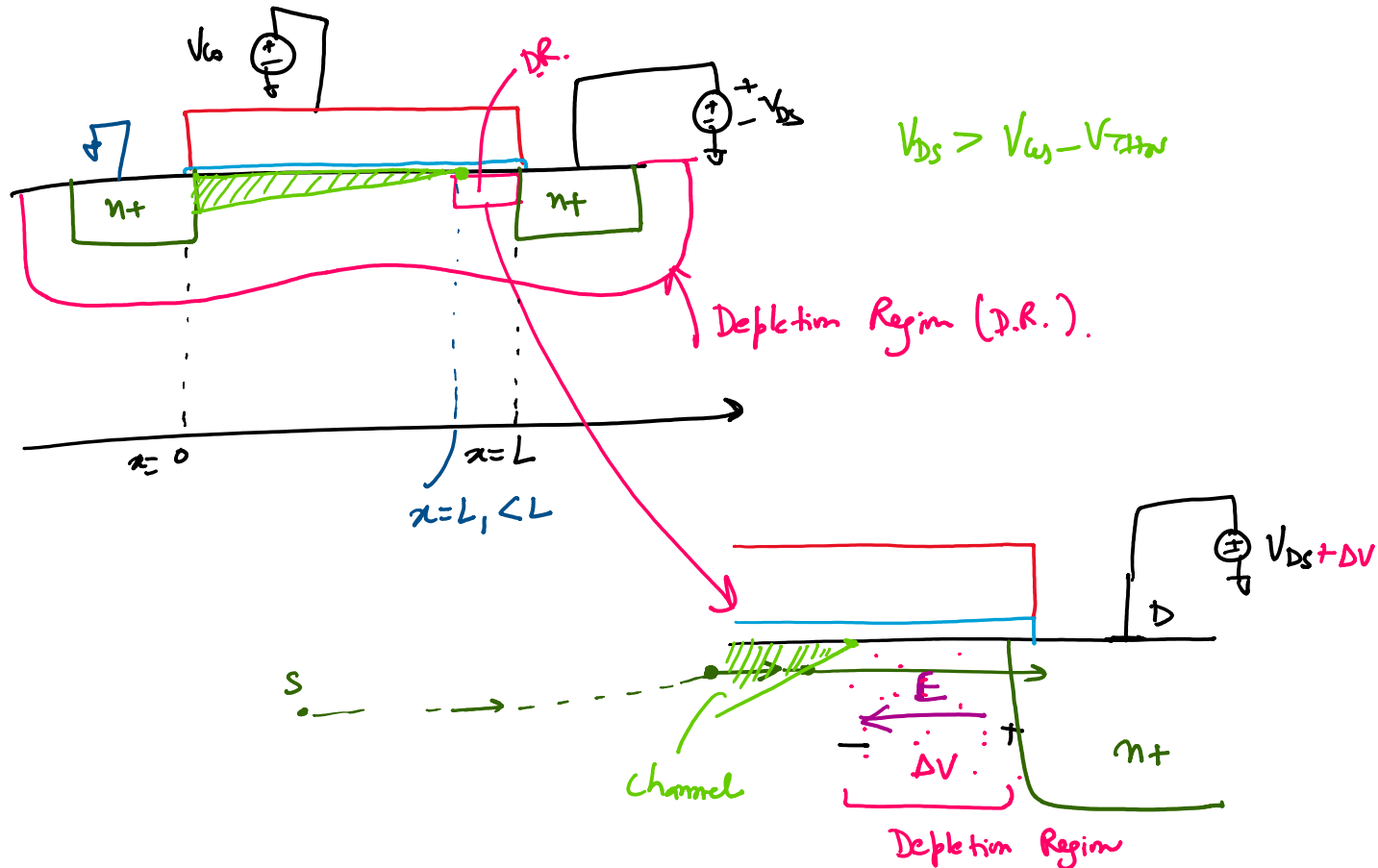
The moment V_{ds} exceeds $V_{gs} - V_{thn}$, pinch off of the channel occurs.

* Beyond pinch off, the channel is no longer continuous between drain & source.



Why does the drain current saturate beyond Pinchoff?

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Most of the voltage drop is across the depletion region (D.R.)
 & once the electrons (from Source) reach the end of the channel,
 they experience high E-field in the D.R.

↳ rapidly swept off to the drain terminal

↳ still we have current flow

↳ drain terminal voltage (V_{DS}) no longer affects this current significantly.

↳ SATURATION of current

I_D
 ↑
 pinch-off → $V_{DS} \uparrow$

